

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Washio et al.
Appl. No.	:	10/578,398
Filed	:	May 4, 2006
For	:	THICK FILM PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Walke, A.
Group Art Unit	:	1795

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **January 9, 2008**, please consider the following amendments and remarks.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 4 of this paper.